




AQUEOUS POLYMER DISPERSION AND USE THEREOF IN COSMETICS**Patent number:** WO2005005497**Publication date:** 2005-01-20**Inventor:** CHRISSTOFFELS LYSANDER (DE); HOESSEL PETER (DE); GARCIA CASTRO IVETTE (DE); WOOD CLAUDIA (DE); ANGEL MAXIMILIAN (DE); MATHAUER KLEMENS (DE)**Applicant:** BASF AG (DE); CHRISSTOFFELS LYSANDER (DE); HOESSEL PETER (DE); GARCIA CASTRO IVETTE (DE); WOOD CLAUDIA (DE); ANGEL MAXIMILIAN (DE); MATHAUER KLEMENS (DE)**Classification:**




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 US2003091602
 US6426383
 US6362245

Report a data error here**Abstract of WO2005005497**

The invention relates to an aqueous polymer dispersion that can be obtained by the radical polymerisation of a monomer mixture consisting of at least one compound containing an amide group, at least one cross-linking agent, and at least one monomer comprising at least one cationogenic and/or cationic group. The invention also relates to the polymers that can be obtained by drying one such polymer dispersion, and to cosmetic or pharmaceutical agents containing one such polymer dispersion or one such polymer.

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